

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	129	(phosphorus sulfur amino) same defect same (mask reticle)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 12:13
L2	16	(phosphorus sulfur amino) with defect with (mask reticle)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 12:16
L3	4	analyz\$4 same defect same electron near microscope with chemical	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 12:21
L4	0	analyz\$4 same defect same electron near microscope with chemical same fourier with transform with infrared with spectroscopy	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 12:22
L5	2	analyz\$4 same defect same electron near microscope with chemical and fourier with transform with infrared with spectroscopy	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:09
L6	2	analyz\$4 same defect and electron near microscope with chemical and fourier with transform with infrared with spectroscopy	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:10
L7	1	analyz\$4 same defect and electron near spectroscop\$3 with chemical and fourier with transform with infrared with spectroscop\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:11
L8	58	electron near spectroscop\$3 with chemical and fourier with transform with infrared with spectroscop\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:11
L9	8	electron near spectroscop\$3 with chemical and fourier with transform with infrared with spectroscop\$3 and defect	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:24
L10	248	reticle near pellicle	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:24
L11	11	reticle near pellicle with scan\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:36

L12	0	presense with (sulfur phosphorus amino) same defect	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:37
L13	155	presence with (sulfur phosphorus amino) same defect	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:44
L14	33	presence with (sulfur phosphorus amino) same defect and (semiconductor wafer mask reticle)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:55
L15	41	predict\$4 same defect same grow\$3 same time	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:43
L16	311	defect same remov\$4 same gaseous	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:43
L17	142	defect same remov\$4 same gaseous and (semiconductor wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:54
L18	3	defect same remov\$4 same gaseous same convert\$4 and (semiconductor wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:00
L19	87	(phan and singh and rangarajan). inv.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:55
L20	4	(phan and singh and rangarajan). inv. and gaseous	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 13:55
L21	28	defect same remov\$4 same gas\$5 same convert\$4 and (semiconductor wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:16
L22	2	defect same remov\$4 same gas\$5 same convert\$4 and (semiconductor wafer) and focused near ion near beam	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:18
L23	1	defect same remov\$4 same gas\$5 same convert\$4 same pump\$4 and (semiconductor wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:15

L24	3	defect same remov\$4 same gas\$5 same convert\$4 and (semiconductor wafer) and ion near beam	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:17
L25	2	defect same remov\$4 same gas\$5 same convert\$4 and (semiconductor wafer) and fib	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:18
L26	105	defect same remov\$4 same gas\$5 and (semiconductor wafer) and focused near ion near beam	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:18
L27	0	presence with (sulfur phosphorus amino) same defect same signature	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:44
L28	8	predict\$4 with defect with grow\$3 with time	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 14:58
L29	46	predict\$4 with defect with grow\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 15:16
L30	16	predict\$4 with defect with grow\$3 and (semiconductor wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 15:18
L31	2	predict\$4 same rate with defect with grow\$3 and (semiconductor wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 15:19
L32	22	predict\$4 same rate same defect same grow\$3 and (semiconductor wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 15:23
L33	83	predict\$4 same defect same grow\$3 and (semiconductor wafer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 15:23
S1	0	scan\$3 with defect and mill\$3 with excis\$3 and signature	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:27
S2	0	scan\$3 same defect and mill\$3 same excis\$3 and signature	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/04/05 14:23

S3	9	detect\$3 same defect and mill\$3 same excis\$3 and signature	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/04/05 14:23
S4	101	detect\$3 same defect and mill\$3 same remov\$3 and (reticle mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/04/05 14:24
S5	32	detect\$3 same defect and mill\$3 same remov\$3 and (reticle mask) and soft	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/04/05 14:24
S6	1	signature with defect with composition and scan\$5 and mill\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/12/02 12:17
S7	1	signature with defect with composition and scan\$5 and remov\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/12/02 12:22
S8	1603	(whitehead and carl).xp.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/12/02 12:22
S9	0	scan\$4 same soft near defect same remov\$4 same analy\$4 same signature	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 13:46
S10	0	scan\$4 same soft near defect same remov\$4 and analy\$4 same signature	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 13:46
S11	5446	pellicle	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 13:46
S12	0	scan\$4 same soft near defect same remov\$4 same analy\$4 and (sulphur phosphorus amino)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 13:47
S13	5	scan\$4 same defect same remov\$4 same analy\$4 and (sulphur phosphorus amino)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 13:49
S14	1284	scan\$4 same defect same remov\$4 S12 and (sulphur phosphorus amino)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 13:49

S15	124	scan\$4 same defect same remov\$4 and (sulphur phosphorus amino)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 13:49
S16	44	scan\$4 same defect same remov\$4 and (sulphur phosphorus amino) and analy\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 14:17
S17	1	scan\$4 same defect same remov\$4 and (sulphur phosphorus amino) and analy\$4 and pellic\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 14:18
S18	1	scan\$4 same defect same remov\$4 and (sulphur phosphorus amino) and analy\$4 and pellic\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 14:18
S19	10	("4716299"   "5796484"   "5900354"   "5940175"   "5989763"   "6097790"   "6279249"   "6327021"   "6363166").PN. OR ("6665065"). URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/02/10 14:43
S20	25	scan\$4 same defect and remov\$4 with defect and analy\$4 and pellic\$4	US-PGPUB; USPAT; USOCR	OR	ON	2005/02/10 14:51
S21	1	scan\$4 same defect and remov\$4 with defect and analy\$4 and pellic\$4 and (sulfur phosphorus amino)	US-PGPUB; USPAT; USOCR	OR	ON	2005/02/10 14:46
S22	0	scan\$4 same defect and excis\$4 with defect and analy\$4 and pellic\$4	US-PGPUB; USPAT; USOCR	OR	ON	2005/02/10 14:48
S23	25	scan\$4 same defect and remov\$4 with defect and analy\$4 and pellic\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 14:52
S24	5	scan\$4 same defect and analy\$4 and pellic\$4 and focused near ion near beam	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/10 14:53
S25	148	detect\$4 same defect same (mask reticle photomask) and (excis\$4 remov\$4) with defect and analy\$4 with defect	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:29
S26	34	detect\$4 same defect same (mask reticle photomask) and (excis\$4 remov\$4) with defect and analy\$4 with defect and focused near ion near beam	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:34

S27	0	detect\$4 same defect same (mask reticle photomask) and (excis\$4 remov\$4) with defect and analy\$4 with defect and focused near ion near beam and (sulfur phosphorus amino)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:29
S28	0	detect\$4 same defect same (mask reticle photomask) and (excis\$4 remov\$4) with defect and analy\$4 with defect and focused near ion near beam and (sulfur phosphorus amino)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:30
S29	4	detect\$4 same defect same (mask reticle photomask) and (excis\$4 remov\$4) with defect and analy\$4 with defect and focused near ion near beam and pellic\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:30
S30	0	detect\$4 same defect same (mask reticle photomask) and (excis\$4) with defect and analy\$4 with defect and focused near ion near beam	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:35
S31	16	detect\$4 same defect same (mask reticle photomask) and (cut\$4) with defect and analy\$4 with defect and focused near ion near beam	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:44
S32	0	detect\$4 same defect same (mask reticle photomask) and (cut\$4) with defect and analy\$4 with defect and focused near ion near beam and pellic\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:39
S33	19	detect\$4 same defect same (mask reticle photomask) and (remov\$4) with defect same focused near ion near beam and analy\$4 with defect	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/16 12:13
S34	0	detect\$4 same defect same (mask reticle photomask) and (remov\$4) with defect same focused near ion near beam and analy\$4 with defect and (sulfur phosphorus amino)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 14:50
S35	19	detect\$4 same defect same (mask reticle photomask (photo near mask)) and (remov\$4) with defect same focused near ion near beam and analy\$4 with defect	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/15 15:01